

FORM PTO - 1449 SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT				ATTORNEY DOCKET NO.: ASC-022CPC1 APPLICANTS: Wu <i>et al.</i> SERIAL NO.: 10/603,852 FILING DATE: June 25, 2003 GROUP: 2811			
U.S. PATENT DOCUMENTS							
EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
DWO	A268	2002/0190284	12/19/2002	Murthy et al.			
	A269	2002/0063292	05/30/2002	Armstrong			
	A270	2002/0167048	11/14/2002	Tweet et al.			
	A271	2004/0007715	01/15/2004	Webb et al.			
	A272	2004/007724	01/15/2004	Murthy et al.			
	A273	2004/0014276	01/22/2004	Murthy et al.			
	A274	2004/0084735	05/06/2004	Murthy et al.			
	A275	2004/0111901	06/24/2004	Schrom et al.			
	A276	4,969,031	11/00/1990	Kobayashi et al.			
	A277	5,013,681	05/07/1991	Kub et al.			
	A278	6,228,694	05/08/2001	Doyle et al.			
	A279	6,235,568	05/22/2001	Murthy et al.			
	A280	6,281,532	08/28/2001	Doyle et al.			
	A281	6,326,664	12/04/2001	Chau et al.			
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	A286	6,605,498	08/12/2003	Murthy et al.			
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	A289	6,657,223	12/02/2003	Wang et al.			
DWO	A290	6,674,150	01/06/2004	Takagi et al.			
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DWO	A291	6,703,648	03/09/2004	Xiang					
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DWO	A293	6,790,747	09/14/2004	Henley <i>et al.</i>					
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<i>OK</i>	B55	0 828 296 A	03/11/1998	EP					
OTHER ART, JOURNAL ARTICLES, ETC.									
EXAM. INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)								
	C167	International Search Report and Written Opinion from the International Examining Authority for related application PCT/US01/19613, dated June 22, 2002							
DWO	C168	Kuboto M., <i>et al.</i> "New SOI CMOS Process with Selective Oxidation," IEEE IEDM TECH, DIG., pp. 814-816 (1986)							
DWO	C169	Ming <i>et al.</i> , "Interfacial roughness scaling and strain in lattice mismatched Si _{0.4} Ge _{0.6} thin films on Si" Applied Physics Letters, Vol. 67, No. 5, July 31, 1995, pp. 629-631							
DWO	C170	Ming <i>et al.</i> , "Microscopic structure of interfaces in Si _{1-x} Gex/Si heterostructures and superlattices studied by x-ray scattering and fluorescence yield," Physical Review B, Vol. 47, No. 24, pp. 373-81, June 15, 1993							
DWO	C171	Nishi <i>et al.</i> "Handbook of Semiconductor Manufacturing Technology," Marcel Dekker AG, New York, NY, 2000 pp. 1-22							
DWO	C172	O'Neill, <i>et al.</i> , "Deep Submicron CMOS Based on Silicon Germanium Technology," Fellow, IEEE Transactions on Electron Devices, Vol. 43, No. 6, June 1996 pp. 911-918							
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DWO	C173	Sugii, et al., "Role of Si1-xGex buffer layer on mobility enhancement in a strained-Si channel metal-oxide-semiconductor field-effect transistor," Central Research Laboratory, Hitachi Ltd. 1-280 Higashi-Koigakubo, Kokubunji-shi, Tokyo 185-8601 Japan, pp. 2948-2950	
DWO	C174	Vossen et al. "Thin Film Processes II" Academic Press Inc., San Diego, CA 1991, pp. 370-442	
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